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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/769,835	02/02/2004	Srinath Krishnan	039153-0694	9075
26371 FOLEV & LA	7590 06/04/2007 EXAMINER			
FOLEY & LARDNER LLP 777 EAST WISCONSIN AVENUE			MENZ, DOUGLAS M	
MILWAUKE	E, WI 53202-5306		ART UNIT	PAPER NUMBER
			2891	
			MAIL DATE	DELIVERY MODE
			06/04/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

		Application No.	Applicant(s)			
Office Action Summary		10/769,835	KRISHNAN, SRINATH			
		Examiner	Art Unit			
		Douglas M. Menz	2891			
D : 16	The MAILING DATE of this communication app					
Period fo	• •					
VVHIC - Exte after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DATE of time may be available under the provisions of 37 CFR 1.1: SIX (6) MONTHS from the mailing date of this communication. Disperiod for reply is specified above, the maximum statutory period vire to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICAT 36(a). In no event, however, may a reply b will apply and will expire SIX (6) MONTHS to cause the application to become ARANDO.	TON. De timely filed from the mailing date of this communication. ONED (35 U.S.C. & 133)			
Status						
1)	Responsive to communication(s) filed on <u>08 M</u>	arch 2007				
	This action is FINAL . 2b)⊠ This action is non-final.					
3)						
	closed in accordance with the practice under E					
Dispositi	ion of Claims					
4)🖂	Claim(s) <u>1-16 and 21-24</u> is/are pending in the a	application				
	4a) Of the above claim(s) <u>9-16 and 21-24</u> is/are withdrawn from consideration.					
	Claim(s) is/are allowed.					
6)⊠ [`]	☐ Claim(s) 1-8 is/are rejected.					
7)	Claim(s) is/are objected to.					
8)	Claim(s) are subject to restriction and/or	r election requirement.				
Applicati	on Papers					
9)[]	The specification is objected to by the Examine	r				
	The drawing(s) filed on <u>02 February 2004</u> is/are		cted to by the Examiner			
	Applicant may not request that any objection to the					
	Replacement drawing sheet(s) including the correct		, ,			
11)	The oath or declaration is objected to by the Ex					
	ınder 35 U.S.C. § 119					
12)	Acknowledgment is made of a claim for foreign	priority under 35 U.S.C. § 119	∂(a)-(d) or (f).			
a)[☐ All b) ☐ Some * c) ☐ None of:					
	1. Certified copies of the priority documents have been received.					
	2. Certified copies of the priority documents					
	3. Copies of the certified copies of the prior		eived in this National Stage			
* 0	application from the International Bureau	•				
	See the attached detailed Office action for a list	or the certified copies not rece	IVed.			
Attachmen	t(s)					
_	e of References Cited (PTO-892)	4) 🔲 Interview Summ	ary (PTO-413)			
2) 🔲 Notic	e of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mai	il Date			
3) [_] Inforr Pape	nation Disclosure Statement(s) (PTO/SB/08) r No(s)/Mail Date	5) Notice of Information Other:	al Patent Application			

U.S. Patent and Trademark Office PTOL-326 (Rev. 08-06) Application/Control Number: 10/769,835

Art Unit: 2891

DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-5 are rejected under 35 U.S.C. 102(b) as being anticipated by Park et al. (US 6482715).

Regarding claim 1, Park discloses a method of manufacturing an integrated circuit having trench isolation regions in a substrate, the method comprising:

Forming a mask layer (104, Fig. 3A) above the substrate;

Selectively etching the mask layer to form apertures associated with locations of the trench isolation regions (104, Fig. 3A);

Forming trenches (106a-b, Fig. 3A) in the substrate at the locations;

Forming first type liners (108, Figs. 3E-G) on first side walls of the trenches associated with first type regions of the substrate (Cols. 4-5); and

Forming second type liners (comprising 108, 110, 112, Figs. 3E-G) on second side walls of the trenches associated with second type regions (Cols. 4-5), wherein the first type liners are disposed directly on the first sidewalls and the second type liners are disposed directly on the second side walls (Figs. 3E-G).

Application/Control Number: 10/769,835

Art Unit: 2891

Regarding claim 2, Park further discloses providing an insulative material (116) in the trenches to form trench isolation regions (Figs. 3F-G).

Regarding claim 3, Park further discloses removing the insulative material (116) until a silicon nitride layer (104) is reached (Fig. 3F).

Regarding claim 4, Park further discloses wherein the first type liners are a first thickness and the second type liners are a second thickness, the second thickness being different than the first thickness (Fig. 3G).

Regarding claim 5, Park further discloses wherein the first type liners (108) are dry oxide material (Col. 4) and the second type liners (110) are dry heavily nitrided oxide material (Col. 5).

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 6-8 are rejected under 35 U.S.C. 103(a) as being unpatentable over Park et al. (US 6482715) in view of Lee et al. (US 6737706).

Art Unit: 2891

2801

Regarding claims 6-7, Park discloses the method of claim 1 as mentioned above, however, Park does not explicitly disclose wherein the substrate is on an SOI substrate as in regards to claim 6 or that the substrate trenches reach a buried insulative layer of the substrate as in regards to claim 7. Lee discloses that it is known in the art to form trench isolation features (41) on SOI substrates (30) wherein the trenches reach the buried insulative layer (15) (Fig. 1 and Col. 1). It would have been obvious to one of ordinary skill in the art to implement Park's method with a SOI substrate as taught by Lee because Lee explicitly discloses in the background section that such teachings are conventional.

Regarding claim 8, Park discloses the method of claim 1 as mentioned above and further discloses a first and second region (P and N type), however, Park does not explicitly disclose wherein the substrate includes a strained silicon layer. It would have been obvious to one of ordinary skill in the art at the time the invention was made to incorporate Park's teachings with a strained silicon layer because doing so was well known in the art at the time of the invention.

Response to Arguments

Applicant's arguments filed 2/6/07 have been fully considered but they are not persuasive. Applicant has amended claim 1 to include the limitation "wherein the first

Art Unit: 2891

type liners are disposed directly on the first sidewalls and the second type liners are disposed directly on the second side walls" and argues that Park does not disclose such limitation. Examiner disagrees. As stated in the above rejection, Park discloses a first type of liner formed in region A2, Fig. 3G, consisting of layer 108, Fig. 3G and a second type of liner formed in region A1, Fig. 3G, consisting of layers 108, 110 and 112, Fig. 3G. Therefore, the liner of the first type (108) is disposed directly on the first sidewalls (Fig. 3G) and the liner of the second type (composite liner consisting of layers 108, 110 and 112) is also disposed directly on the second sidewalls (Fig. 3G).

Applicant's claim language states "first type liners" and "second type liners". Such broad claim language would include composite liners of more than one layer, which is explicitly disclosed in Fig. 3G.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Douglas M. Menz whose telephone number is 571-272-1877. The examiner can normally be reached on M-F 8-5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Bill Baumeister can be reached on 571-272-1722. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Art Unit: 2891

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

DM

DOUGLAS M. MENZ
PRIMARY PATENT EXAMINER